2022년 1월 25일(화), 10:45-12:30
Room J (하트 III, 6층)

B. Patterning 분과

[TJ2-B] 포토리소그래피 II

좌장: 정현담 교수(전남대학교), 이상설 박사(포항가속기연구소)

TJ2-B-1 **10:45-11:15**	**Development of Photolithographic Process based on Fluorinated Photoresists for High Resolution OLED Display** Byung Jun Jung[1] and Jin-kyun Lee[2] *[1]University of Seoul, [2]Inha University*
TJ2-B-2 **11:15-11:45**	**Effective Production of Copolymers for Chemically Amplified Resists Enabled by Continuous Flow Polymerization** Myungwoong Kim[1], Jin-Kyun Lee[2], Jiyeong Yeo[1], Jihoon Woo[2], Seungyeon Choi[1], and Kiyoung Kwon[2] *[1]Department of Chemistry and Chemical Engineering, Inha University, [2]Department of Polymer Science and Engineering, Inha University*
TJ2-B-3 **11:45-12:00**	**Characterization of Chemical Reaction of EUV Exposed HSQ Resist with Micro- to Nano-infrared Spectroscopy** Jiho Kim[1], IL Hyoung Lee[2], Kanghyun Kim[1], Dong Gun Lee[2], Boknam Chae[1], and Sangsul Lee[1] *[1]Phohang Accelerator Laboratory, POSTECH, [2]ESOL, Inc.*
TJ2-B-4 **12:00-12:15**	**Fluorinated Extreme UV Resists based on Radical Chemistry** Ye-Jin Ku[1], Sangsul Lee[2], Byung Jun Jung[3], and Jin-Kyun Lee[1] *[1]Program in Environment and Polymer Engineering, Inha University, [2]Pohang Accelerator Laboratory, POSTECH, [3]Department of Materials Science and Engineering, University of Seoul*
TJ2-B-5 **12:15-12:30**	**노광 공정 중 EUV 펠리클의 EUV 투과도 저하 원인 연구** 위성주[1,3], 김하늘[1,3], 김창수[2,3], 강영우[1,3], 김원진[1,3], 안진호[1,2,3] *[1]한양대학교 신소재공학과, [2]한양대학교 나노융합과학과, [3]EUV-IUCC (Industry University Collaboration Center)*